

**Semi-Aqueous Photoresist or Semiconductor Manufacturing Residue Stripping
and Cleaning Composition with Improved Silicon Passivation**

ABSTRACT OF THE DISCLOSURE

5 A photoresist or semiconductor manufacturing residue stripping and cleaning composition comprising water, one or more alkaline compounds, one or more corrosion inhibitors, and one or more oxidized products of one or more antioxidants, the method of making the composition and the method of using the composition.